

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-343746

(43)Date of publication of application : 14.12.2001

(51)Int.CI.

G03F 7/033
C08K 5/28
C08L 33/00
C08L 39/06
C08L 57/00
G03F 7/008
H01J 9/227

(21)Application number : 2000-164542

(71)Applicant : SANYO CHEM IND LTD

(22)Date of filing : 01.06.2000

(72)Inventor : WATANABE TETSUYA
SHIONO KAZUJI
MUKAI TAKAO

(54) PHOTORESISTIVE COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a photosensitive composition having proper adhesiveness with respect to a glass surface and in aging stability and is suitable for use in the formation of the black matrix of a color cathode-ray tube.

SOLUTION: The photosensitive composition comprises 70-99.5 mass% water-soluble vinyl copolymer (A) comprising the units of a water-soluble monomer (a), having a group selected from among a carboxylic acid group, an acid anhydride group, a sulfonic acid group, a phosphoric acid group and their salts, and N-vinylpyrrolidone units and 0.5-30 mass% water-soluble azido compound (B).

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office